

L Number	Hits	Search Text	DB	Time stamp
1	266	electron adj beam adj microscope	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/06 10:30
3	138	(electron adj beam adj microscope) and substrate	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/06 10:31
4	74	((electron adj beam adj microscope) and substrate) and wafer	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/06 10:31
6	67	((electron adj beam adj microscope) and substrate) and wafer) and semiconductor	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/06 10:32
7	35	((electron adj beam adj microscope) and substrate) and wafer) and semiconductor) and inspection	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/06 10:33
10	2	(electron adj beam adj microscope) and ((low adj energy adj electron adj microscope) or LEEM)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/06 10:35
9	2	((electron adj beam adj microscope) and substrate) and wafer) and semiconductor) and inspection) and ((low adj energy adj electron adj microscope) or LEEM)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/06 10:46
8	20	((electron adj beam adj microscope) and substrate) and wafer) and semiconductor) and inspection) and review	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/06 10:46
11	2	((electron adj beam adj microscope) and substrate) and wafer) and semiconductor) and inspection) and review) and ((low adj energy adj electron adj microscope) or LEEM)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/06 10:47